



GENESIS MATERIAL TECHNOLOGY

895-F Hampshire Road, Stow, Ohio, 44224

Office: (330) 920-8550 Fax: (330) 920-8551

www.genesismt.com

AQ 3000 Waterborne Photoresist

Product Highlights



- **Liquid Negative Acting Photoresist**
- **Sub 1 Mil Features Possible**
- **Designed For Etching in Cupric & Ferric Chloride**
- **Super Fast UV Exposures – 20 mJ and lower - 4 X Faster**
- **LDI Compatible**
- **Dries in 3-5 Minutes - 5 X Faster**
- **Compatible with Existing Equipment and Processes**
- **Overcomes Major Bottlenecks in Imaging Process**
- **Surpasses Dry Film Adhesion to All Metals**
- **Waterborne, User Friendly, No Solvent Smell**
- **VOC Free, Environmentally Friendly**
- **Cleans Up in Soap and Water, No Solvents Necessary**
- **Significant Savings Compared to Dry Film**
- **100% OSHA Approved Materials**
- **Approved by Major Manufacturers**